

INFORMATION DISCLOSURE CITATION (Use several sheets if necessary)				Docket Number (Optional) 2002US36	Application Number 10/042,532			
				Applicant(s) Joseph E. Oberlander et al	Filing Date January 9, 2002	Group Art Unit 1733		
U.S. PATENT DOCUMENTS								
EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS		
COPY OF PAPERS ORIGINALLY FILED								
FOREIGN PATENT DOCUMENTS								
	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
							YES	NO
EA		DE 41 12 967 A1	10/22/1992	Germany				X
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)								
								
EXAMINER <i>P. Ashton</i>				DATE CONSIDERED <i>7/15/03</i>				

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U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	TRADEMARK OFFICE	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
ZIA		4,491,628	01/01/1985	Hiroshi Ito et al			
		4,521,274	06/04/1985	Elsa Reichmanis et al			
		4,557,797	12/10/1985	Gene E. Fuller et al			
		4,863,827	09/05/1989	Sangya Jain et al			
		4,910,122	03/20/1990	John W. Arnold et al			
		5,069,997	12/03/1991	Reinhold Schwain, et al			
		5,350,660	09/27/1994	Fumiyoji Urano et al			
		5,354,643	10/11/1994	Ivan Cabrera et al			
		5,581,730	12/03/1996	Mark Silla			
		5,585,219	12/17/1996	Yuko Kaimoto et al			
ZIA		5,635,333	06/03/1997	John S. Peterson et al			

FOREIGN PATENT DOCUMENTS

EXAMINER INITIAL	TRADEMARK OFFICE	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
ZIA		EP 0 794,458		Europe				
		GB 2320718		Great Britain				
		EP 583,205		Europe				
		EP 542,008		Europe				
ZIA		GB 2135 793		Great Britain				

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

ZIA	K. Bather et al, "TiN, O, As a Barrier Between Cr-Si-(O) and Aluminum Thin Films", Thin Solid Films, 200 (1991) pg 93 - 117
ZIA	C. Nolscher et al, "High contract single layer resists and antireflection layers – an alternative to multilayer resist techniques", SPIE Vol. 1086 Advances in Resist Technology and Processing VI (1989) pg 242 - 250

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R. Ashton

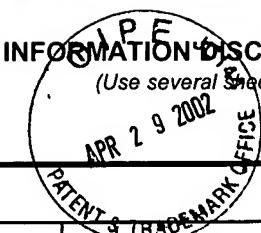
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## U.S. PATENT DOCUMENTS

*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
RA		5,652,297	07/29/1997	Iain McCulloch et al			
		5,716,756	02/10/1998	Georg Pawlowski et al			
		5,731,386	03/24/1998	James W. Thackeray et al			
		5,763,135	06/09/1998	Shuji Ding et al			
		5,880,169	03/09/1999	Yolchi Osawa et al			
		5,882,996	03/16/1999	Chang-Ming Dal			
		5,886,102	03/23/1999	Roger E. Sinta et al			
		5,935,760	08/10/1999	Xie Shao et al			
		5,939,236	08/17/1999	Edward K. Pavelcheck et al			
RA		5,981,145	11/09/1999	Shuji Ding et al			

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## FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
RA		DE 3,930,086		Germany				X
		DE 3,930,087		Germany				X
		DE 4,112,967.9		Germany				X
RA		EP 0 813 114		Europe				

## OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

RA	G. Czech et al, "Reduction of Lindwidth Variation for the Gate Conductor Level by Lithography Based on a New Antireflective Layer", Microelectronic Engineering 21 (1993) pages 51 - 56
RA	F. M. Houlihan et al, "Chemically Amplified Resists: The Chemistry and Lithographic Characteristics of Nitrobenzyl Benzenesulfonate Derivatives", Journal of Photopolymer Science and Technology, Volume 3, No. 3 (1990) pages 259 - 273

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				FILING 01/09/2002	GROUP NOT ASSIGNED-		
U.S. PATENT DOCUMENTS							
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS SUBCLASS		
RA		6,042,990	03/28/2000	Xie Shao et al			
		6,080,530	07/27/2000	Xie Shao et al			
		6,110,653	08/29/2000	Steven J. Holmes et al			
		6,114,085	09/05/2000	M. Padmanaban et al			
		6,187,506	02/13/2001	Shuji Ding et al			
		6,242,161	06/05/2001	Kazuo Kawaguchi et al			
RA		6,251,562	06/26/2001	Gregory Breyta et al			
FOREIGN PATENT DOCUMENTS							
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS SUBCLASS	TRANSLATION	
RA		GB 2357 509 A	06/27/2001	Europe		YES	NO
RA		WO 97/33198	09/12/1997	Europe			
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)							
RA			T. Yamaoka et al, "Photochemical Dissociation of p-Nitrobenzyl Aromatic Sulfonate and Its Application to Chemical Amplification Resists", Journal of Photopolymer Science and Technology, Volume 3, No. 3 (1990) pages 275 - 280				
RA			Masamitsu Shirai et al, "Photochemistry of Imino Sulfonate Compounds and Their Application to Chemically Amplified Resists", Journal of Photopolymer Science and Technology, Volume 3, No. 3 (1990) pages 301-304				
EXAMINER			DATE CONSIDERED				
<i>Johnston</i>						<i>7/15/03</i>	

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<b>U.S. PATENT DOCUMENTS</b>							
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						<i>MAY 9 2002</i> <i>TC J 100</i>	
<b>FOREIGN PATENT DOCUMENTS</b>							
	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
<b>OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)</b>							
<i>RA</i>			Leo Schlegel et al, "Studies on the Acid Formation and Deprotection Reaction by Novel Sulfonates in a Chemical Amplification Positive Photoresist", Journal of Photopolymer Science and Technology, Volume 3, No. 3 (1990) pages 281 - 287				
<i>RA</i>			James Fahey et al, "Design of a Bottom Anti-Reflective Layer for Optical Lithography", SPIE, Vol. 2195, pages 422 - 2195				
EXAMINER			DATE CONSIDERED				
<i>R Ashton</i>			<i>7/13/03</i>				

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